

Abstract

A resist transfer pad and method of use are described for forming a uniform
5 photoresist on the surface of a workpiece such as a slider. The resist transfer pad
includes a layer of cured polydimethylsiloxane (**PDMS**) on a cushioning layer, e.g.
silicone rubber, and an optional stiffening layer. The sliders are preferably mounted on a
carrier or pallet. In one preferred embodiment the loaded resist transfer pads are applied
10 to the slider surface by roll lamination where the loaded resist transfer pad is transported
by a roller system using a cover-tape and pressed against the slider surface. Subsequently
the cover-tape and the resist transfer pad are lifted off and the photoresist remains on the
transducer. An alternative embodiment uses a vacuum, piston laminator to press the
loaded resist transfer pad onto the surface of the transducer.

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